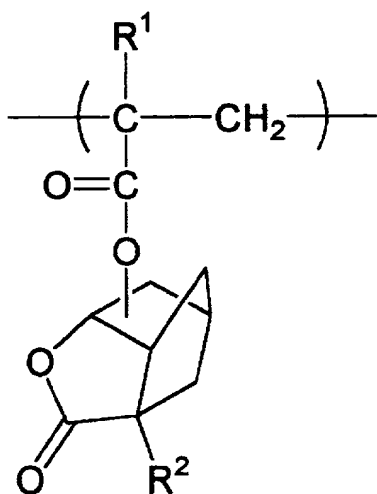


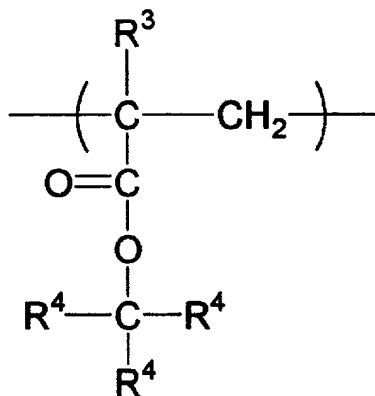
WHAT IS CLAIMED IS:

1. A radiation-sensitive resin composition comprising:

(A) an acid-dissociable group-containing resin which is
5 insoluble or scarcely soluble in alkali and becomes alkali
soluble when the acid-dissociable group dissociates, the resin
comprising the recurring unit of the following formula (1) and
the recurring unit of the following formula (2),



(1)



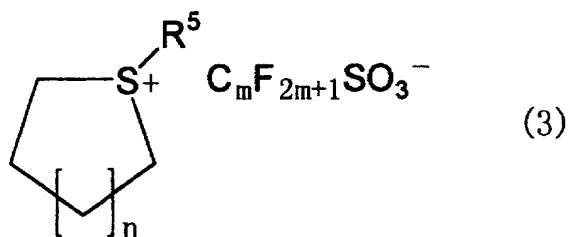
(2)

10

wherein R¹ and R² individually represent a hydrogen atom or
methyl group, R³ represents a hydrogen atom or methyl group,
and R⁴ individually represents a linear or branched alkyl group
having 1-4 carbon atoms or a monovalent alicyclic hydrocarbon
15 group having 4-20 carbon atoms or a derivative thereof, or any

two of R⁴ groups form in combination a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, with the remaining R⁴ group being a linear or branched alkyl group having 1-4 carbon atoms or a monovalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof, and

(B) a photoacid generator of the following formula (3),



wherein R⁵ represents a monovalent aromatic hydrocarbon group having 6-20 carbon atoms or a derivative thereof, m is an integer of 1-8, and n is an integer of 0-5.

2. The radiation-sensitive resin composition according to claim 1, wherein any two of the R⁴ groups in the formula (2) form, in combination and together with the carbon atom with which these groups bond, a divalent alicyclic hydrocarbon group having 4-20 carbon atoms or a derivative thereof and the remaining R⁴ group is a linear or branched alkyl group having 1-4 carbon atoms.

3. The radiation-sensitive resin composition according to claim 1, wherein R^4 in the formula (2) or the group formed by any two of the R^4 groups is an alicyclic group derived from norbornane, tricyclodecane, tetracyclododecane, or adamantane or a group in which a hydrogen atom on the aliphatic ring is replaced by an alkylene group.

4. The radiation-sensitive resin composition according to claim 1, wherein the recurring unit of the formula (2) is a recurring unit originating from 2-methyl-2-adamantyl (meth)acrylate or 2-norbornyl-2-n-propyl (meth)acrylate.

5. The radiation sensitive resin composition according to claim 1, wherein the amount of the recurring unit of the formula (1) and the recurring unit of the formula (2) is respectively 10-80 mol% and 10-80 mol% of all recurring units in the resin (A).

6. The radiation-sensitive resin composition according to claim 1, wherein R^5 in the formula (3) is at least one group selected from the group consisting of a 3,5-dimethyl-4-hydroxyphenyl group, 4-methoxyphenyl group, 4-n-butoxyphenyl group, 2,4-dimethoxyphenyl group, 3,5-dimethoxyphenyl group, and 4-n-butoxy-1-naphthyl group.

7. The radiation-sensitive resin composition according to claim 1, wherein m in the formula (3) is 4 or 8.

8. The radiation-sensitive resin composition according to claim 1, wherein n in the formula (3) is 1.

9. The radiation-sensitive resin composition according to claim 1, further comprising a photoacid generator other than the photoacid generator (B) of the formula (3).

10. The radiation-sensitive resin composition according to claim 9, wherein the amount of the photoacid generator other than the photoacid generator (B) is 80 wt% or less of the total amount of the photoacid generators.

11. The radiation-sensitive resin composition according to claim 1, further comprising an acid diffusion controller.

12. The radiation-sensitive resin composition according to claim 1, wherein the acid diffusion controller is a nitrogen-containing organic compound.

13. The radiation-sensitive resin composition according to claim 1, further comprising an alicyclic additive having an acid-dissociable group.

14. The radiation-sensitive resin composition according to claim 1, further comprising a linear or branched ketone, cyclic ketone, propylene glycol monoalkyl ether acetate, alkyl 2-hydroxypropionate, or alkyl 3-alkoxypropionate as a solvent.